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Sumio IJIMA et al.FILING DATE
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GROUP

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
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FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
	AD						
	AE						

OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)

	AF	Ming Su et al., "Lattice-Oriented Growth of Single-Walled Carbon Nanotubes," J. Phys. Chem. B., Vol. 104, No. 28, pp. 6505 to 6508, (July 2000).
	AG	Yihong Wu et al., "Carbon Nanowalls Grown by Microwave Plasma Enhanced Chemical Vapor Deposition," Adv. Mater., Vol. 14, No. 1, pp. 64-67, table 1, last line, (January 2002).
	AH	L. Rotkina et al., "The Oriented Growth of Carbon Nanotubes on Si(100)," AIP Conference Proceedings, Vol. 591, pp. 247-250, (2001).
	AI	Jing Kong et al., "Synthesis of Individual Single-Walled Carbon Nanotubes on Patterned Silicon Wafers," Nature, Vol. 395, pp 878-881, (1998).
	AJ	Li Ping et al., "Atomic Force Microscopy of Carbon Nanotubes and Nanoparticles," Mater. Res. Soc. Symp. Proc., Vol. 359, pp. 87-91, (1995).
	AK	Z.P. Huang et al., "Growth of Highly Oriented Carbon Nanotubes by Plasma-Enhanced Hot Filament Chemical Vapor Deposition," Applied Physics Letters, Vol. 73, No. 26, pp 3845-3847, (1998).
	AL	H. Hongo et al. "Chemical Vapor Deposition of Single-Wall Carbon Nanotubes on Iron-Film-Coated Sapphire Substrates," Chem. Phys. Letters, Vol. 361, No. 3/4, pp. 349-354 (June 2002).

EXAMINER

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